

## REMARKS

### Allowable Subject Matter

Applicants gratefully acknowledge the Examiner's indication that claims 1-12 recite allowable subject matter.

### Amendments

Claims 1 and 3 are amended to delete superfluous language. Claims 13, 14 and 19 are amended to define R<sup>1</sup> and R<sup>2</sup> as they are defined in allowed claim 1. Claim 19 is also amended to correct obvious typographical errors. These amendments to the claims do not require further search and, moreover, place all of the pending claims in condition for allowance. Entry of the amendments is respectfully requested.

### Rejection under 35 USC §102(b) in view of Allen et al.

Claims 13-15 and 19-20 are rejected as allegedly being anticipated in view of Allen et al. (US 5,985,524). This rejection is respectfully traversed.

As previously discussed, US '524 provides no disclosure or suggestion of a polymer exhibiting a silicon-containing group of the formula -CR<sup>1</sup>R<sup>2</sup>-(CR<sup>3</sup>R<sup>4</sup>)<sub>m</sub>Si (R<sup>5</sup>R<sup>6</sup>R<sup>7</sup>), wherein one of R<sup>1</sup> and R<sup>2</sup> is a cyclic alkyl group or in which R<sup>1</sup> and R<sup>2</sup>, taken together, form an aliphatic hydrocarbon ring in which -CH<sub>2</sub>- may be substituted with a -Si(R<sup>8</sup>)<sub>2</sub>- group. Withdrawal of the rejection is respectfully requested.

### Rejection under 35 USC §103 in view of Allen et al. and Allen et al. and Choi

Claims 16-18 are rejected as allegedly being obvious in view of Allen et al. (US 5,985,524) taken in combination with Allen et al. (US 5,580,694) and Choi (US 6,045,970). This rejection is respectfully traversed.

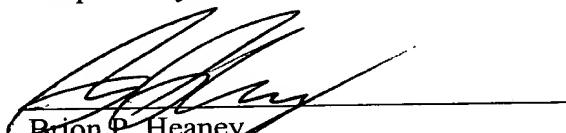
The disclosure of US '524 is discussed above. In the rejection, it is asserted that US '694 discloses the use of dissolution inhibitors. However, US '694 provides no disclosure or suggestion of a polymer in accordance with applicants' claim 14, from which claims 16-18 depend.

With regards to US '970 the rejection asserts that this reference discloses the use of an organic base in a photoresist composition wherein the "organic base prevents a decrease in a critical size of the pattern after exposure, caused by acid diffusing from an exposed portion of

the photoresist to a unexposed portion." But, US '970 provides no disclosure or suggestion of a polymer in accordance with applicants' claim 14.

In view of the above remarks, Allen et al. (US '524), taken alone or in combination with Allen et al. (US '694) and/or Choi (US '970), fails to render obvious applicants' claimed invention. Withdrawal of the rejection is respectfully requested.

Respectfully submitted,



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